

Abstract

Lithographic Projection Apparatus and Device Manufacturing Method

- 5 A lithographic projection apparatus is provided wherein an object situated in a pulsed beam of radiation has an electrode in its vicinity and a voltage source connected either to the electrode or to the object. This configuration can provide a negative voltage pulse to the object relative to the electrode. The beam of radiation and the voltage pulse from the voltage source are provided in phase or out of phase. In this way, the object is
- 10 shielded against secondary electrons generated by radiation beam illumination.